
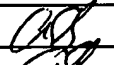
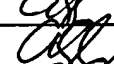

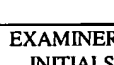

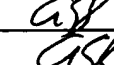
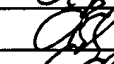
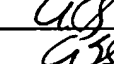
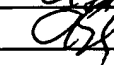

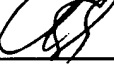


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			APPLICANT Badri N. KRISHNAMURTHY et al.			
			FILING DATE August 14, 2001		GROUP 2171	


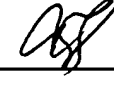
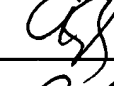

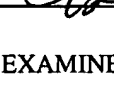
  

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						Yes	No
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August 14, 2001

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						Yes	No
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DATE CONSIDERED	<i>09/05/03</i>

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